

Paper Code: OE-075

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**B. TECH.**  
**(SEM VII) ODD SEMESTER THEORY EXAMINATION 2016-17**  
**MICRO & SMART SYSEM**

[Time: 3 hrs.]

[Max. Marks: 100]

**Note- Attempt All Questions. All Questions carry equal marks:-****Q1 Attempt any four parts of the following:- [5x4=20]**

- (a) What are Microsystems and MEMS?
- (b) Draw the block diagram of a Smart system.
- (c) Enlist the list of smart materials and structures used in micro systems.
- (d) Classify the Integrated micro system and explain each of them in short.
- (e) Discuss some applications of smart materials and micro systems.
- (f) Define micro-sensor and micro-actuator.

**Q2. Attempt any four parts of the following:- [5x4=20]**

- (a) Enlist the advantages and applications of silicon capacitive Accelerometer
- (b) Define piezoresistive pressure sensor? Also give some applications and its advantages.
- (c) How conductor metric gas sensor works?
- (d) Define an electrostatic comb-drive and explain its application.
- (e) Give the principle of operation of portable blood analyzer.
- (f) Fabrication of Micro-mirror array for video projection

**Q3. Attempt any two parts of the following:- [10x2=20]**

- (a) Draw the flow chart of various processes involved in the fabrication of micro systems. Explain each process in short.
- (b) Derive an expression for the thickness of silicon consumed while forming a  $1\mu\text{m}$  thick oxide layer. A (100) silicon wafer is  $500\mu\text{m}$  thick. A mask consists of rectangular window of unknown size. The sides of the window are parallel to  $\langle 100 \rangle$ . After each wafer etch a hole size of  $50\mu\text{m} \times 80\mu\text{m}$  is formed on the other side of the wafer. Find the size of the mask window. The undercut rate is negligible.
- (c) Explain the various advanced processes for microfabrication in brief with suitable diagrams.

**Q4. Attempt any two questions of following:- [10x2=20]**

- (a) In a plane-strain condition, all the strains involving the z-direction are zero. Derive the stress-strain relationship between stress and strains in the x and y directions.
- (b) Explain the principle of energy method for elastic bodies with diagram. Also explain bimorph effect.
- (c) Explain the working principle of spring restrained parallel-plate capacitor for coupled electromechanics. Give its applications.

**Q5. Write short note on any three parts of the following - [20]**

- (a) Scaling effect in Microsystems.
- (b) Microsystems packaging challenges and possible solutions.
- (c) Smart structures in vibration control.
- (d) Piezoelectric inkjet print head